



PTO/SB/08A (10-01)

Approved for use through 10/31/2002. OMB 0651-0031

U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449A/PTO		Complete if Known			
		Application Number	10/666,671		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Filing Date	9/17/03		
		First Named Inventor	Shi		
		Art Unit	1765		
		Examiner Name	Not Yet Assigned		
Sheet	1	of	10	Attorney Docket Number	P118-US

U.S. PATENT DOCUMENTS					
Examiner Initials [*]	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
LV	AA	US- 3,511,727	05-12-1970	Hays, R.G.	
	AB	US- 4,190,488	02-26-1980	Winters, H.F.	
	AC	US- 4,310,380	12-12-1982	Flamm et al.	
	AD	US- 4,498,953	02-12-1985	Cook et al.	
	AE	US- 4,695,700	09-22-1987	Provence et al.	
	AF	US- 4,740,410	04-26-1988	Muller et al.	
	AG	US- 4,749,440	06-07-1988	Blackwood et al.	
	AH	US- 4,789,426	12-06-1988	Pipkin, M.A.	
	AI	US- 5,206,471	04-27-1993	Smith, D.K.	
	AJ	US- 5,330,301	07-19-1994	Brancher, C.D.	
	AK	US- 5,439,553	08-08-1995	Grant et al.	
	AL	US- 5,534,107	07-09-1996	Gray et al.	
	AM	US- 5,672,242	09-30-1997	Jen, J.	
	AN	US- 5,716,495	02-10-1998	Butterbaugh et al.	
	AO	US- 5,726,480	03-10-1998	Pister, K.S.	
	AP	US- 5,753,073	05-19-1998	Jen, J.	
	AQ	US- 5,757,456	05-26-1998	Yamazaki et al.	
	AR	US- 5,835,256	11-10-1998	Huibers, A.	
	AS	US- 5,858,065	01-12-1999	Li et al.	
	AT	US- 6,022,456	02-08-2000	Manning	

FOREIGN PATENT DOCUMENTS						
Examiner Initials [*]	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)				
LV	BA	EP-0704884-A2	04-03-1996	Mehta, J.		
	BB	EP-0822582-A2	02-04-1998	Bhardwai, J.K.		
	BC	EP-0822584-A2	04-04-1998	Bhardwai, J.K.		
	BD	EP-0838839-A2	04-29-1998	Bhardwai, J.K.		
	BE	EP-0878824-A2	11-18-1998	McQuarrie et al.		
	BF	EP-0878824-A3	01-19-2000	McQuarrie et al.		
	BG	EP-0955668-A2	11-10-1999	Yao et al.		
	BH	WO-98/05605	02-12-1998	Bhardwai, J.K.		
	BI	WO-98/13856	04-02-1998	Bhardwai, J.K.		
	BJ	WO-98/32163	07-23-1998	Tai et al.		

Examiner Signature		Date Considered	5/10/05
-------------------------------	--	----------------------------	---------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449A/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	10/666,671
		Filing Date	9/17/03
		First Named Inventor	Shi
		Art Unit	1765
		Examiner Name	Not Yet Assigned
Sheet 2 of 10	Attorney Docket Number	P118-US	

U.S. PATENT DOCUMENTS					
Examiner Initials ¹	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
LV	AU	US- 6,051,503	04-18-2000	Bhardwaj, J.K.	
	AV	US- 6,162,367	12-19-2000	Tai et al.	
	AW	US- 6,277,173 B1	08-21-2001	Sadakata et al.	
	AX	US- 6,290,884 B1	09-18-2001	Patel et al.	
	AY	US- 6,328,801 B1	12-11-2001	Gary et al.	
	AZ	US- 6,334,928 B1	03-12-2002	Sekine et al.	
	AA	US- 6,355,181 B1	03-12-2002	McQuarrie, A.D.	
	AAB	US- 2001/0002663 A1	06-07-2001	Tai et al.	
	AAC	US- 2002/0033229 A1	03-21-2002	Leboulitz et al.	
		US- 2003/0054588	03-20-2003	Patel, et al.	
		US- 2002/0185699	12-12-2002	Reid	
		US- 2002/0121502	09-15-2002	Patel, et al.	
		US- 2002/0047172	04-25-2002	Reid	
		US- 6,436,229	08-20-2002	Tai, et al.	
		US-			
		US- 2002/0196524	12-26-2002	Huibers, et al.	
		US- 2003/0166342	09-04-2003	Chinn, et al.	
		US- 6,409,876	6-25-2002	McQuarrie, et al.	
		US- 6,398,619	5-28-2002	Huibers, et al.	
		US- 6,576,489	6-10-2003	Leung	

FOREIGN PATENT DOCUMENTS						
Examiner Initials ¹	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)				
LV	BK	WO-99/01887	01-14-1999	Lea et al.		
	BL	WO-99/03313	01-21-1999	Lea et al.		
	BM	WO-99/49506	09-30-1999	McQuarrie, A.D.		
	BN	WO-00/52740	08-08-2000	Bhardwaj et al.		
	BO	JP-1982/57098679-A	06-18-1982	Tsunetoshi, A.		
	BP	JP-1983/58130529-A	08-04-1983	Yoshihiro et al.		
	BQ	JP-1985/60057938-A	04-03-1985	Katsumi et al.		
	BR	JP-1986/61053732-A	03-17-1986	Arata et al.		
	BS	JP-1986/61134019-A	06-21-1986	Shinji et al.		
	BT	JP-1986/61181131-A	08-13-1986	Shinji et al.		

Examiner Signature		Date Considered	5/10/05
-----------------------	--	--------------------	---------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Complete if Known	
Sheet		3	of	10	Application Number 10/666,671
					Filing Date 9/17/03
					First Named Inventor Shi
					Art Unit 1765
					Examiner Name Not Yet Assigned
					Attorney Docket Number P118-US

U.S. PATENT DOCUMENTS					
Examiner Initials ¹	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
LV <					

FOREIGN PATENT DOCUMENTS						
Examiner Initials ¹	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)				
LV	BU	JP-1986/61187238-A	08-20-1986	Nobuo et al.		
	BV	JP-1986/61270830-A	12-01-1986	Toru, T.		
	BW	JP-1987/62071217-A	04-01-1987	Toru et al.		
	BX	JP-1988/63155713-A	06-28-1988	Tadashi, F.		
	BY	JP-1989/01208834-A	08-22-1989	Nobuo et al.		
	BZ	JP-1989/10217921-A	08-31-1989	Tsuneo et al.		
	CA	JP-1990/02250323-A	10-08-1990	Susumu et al.		
	CB	JP-1991/03012921-A	01-21-1991	Nobuo et al.		
	CC	JP-1992/04096222-A	03-27-1992	Atsuyuki, A.		
	CD	JP-1995/07029823-A	01-31-1995	Hiroshi, T.		

Examiner Signature	Date Considered 5/10/05
-----------------------	----------------------------

¹ EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

² Applicant's unique citation designation number (optional). ³ See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ⁴ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁵ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁶ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁷ Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Substitute for form 1449A/PTO

(use as many sheets as necessary)

Sheet 4 of 10

Application Number	10/666,671
Filing Date	9/17/03
First Named Inventor	Shi
Art Unit	1765
Examiner Name	Not Yet Assigned
Attorney Docket Number	P118-US

[illegible]

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. 1	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
		Country Code 3 -Number 4 - Kind Code 5 (if known)				
W /	CE	JP-1997/09251981-A	09-22-1997	Kazuaki et al.		
	CF	JP-1998/10313128-A	11-24-1998	Hanmin et al.		
	CG	JP-1998/10317169-A	12-02-1998	McQuarrie et al.		

**Examiner
Signature**

Date Considered

5/10/08

¹ Applicant's unique citation designation number (optional). ² See Kind Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. **DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.**

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449B/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	10/666,671
		Filing Date	9/17/03
		First Named Inventor	Shi
		Group Art Unit	1/65
		Examiner Name	Not Yet Assigned
Sheet	5	of	10
		Attorney Docket Number	P118-US

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
LV	DA	ALIEV et al., "Development of Si(100) Surface Roughness at the Initial Stage of Etching in F2 and XeF2 Gases Ellipsometric Study", Surface Science 442 (1999), pp. 206-214.	
	DB	GLIDEMEISTER, J.M., "Xenon Difluoride Etching System" (Nov. 17, 1997).	
	DC	HABUKA et al., "Dominant Overall Chemical Reaction in a Chlorine Trifluoride-Silicon-Nitrogen System at Atmospheric Pressure", Japan Journal of Applied Physics Vol. 38 (1999), pp. 6466-6469.	
	DD	HECHT et al., "A Novel X-ray Photoelectron Spectroscopy Study of the Al/SiO2 Interface", J. Appl. Phys. Vol. 57 (June 15, 1985), pp. 5256-5261.	
	DE	HOULE, F.A., "Dynamics of SiF4 Desorption During Etching of Silicon by XeF2", IBM Almaden Research Center (April 15, 1987), pp. 1866-1872.	
	DF	FLAMM et al., "XeF2 and F-Atom Reactions with Si: Their Significance for Plasma Etching", Solid State Technol. 28, 117 (1983).	
	DG	IBBOTSON et al., "Plasmaless Dry Etching of Silicon with Fluorine-containing Compounds", J. Appl. Phys. Vol. 56 No. 10 (Nov. 1984), pp. 2939-2942.	
	DH	IBBOTSON et al., "Comparison of XeF2 and F-atom Reactions with Si and SiO2", Applied Physics Letter, Vol. 44, 1129 (1984).	
	DI	STRELLER et al., "Selectivity in Dry Etching of Si (100) and XeF2 and VUV Light", Elsevier Science B.V., Applied Surface Science Vol. 106 (1996), pp. 341-346.	
	DJ		
DK			

Examiner Signature		Date Considered	5/10/05
--------------------	---	-----------------	---------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449B/PTO			Complete if Known		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)			Application Number	10/666,671	
			Filing Date	9/17/03	
			First Named Inventor	Shi	
			Group Art Unit	1765	
			Examiner Name	Not Yet Assigned	
Sheet	6	of	10	Attorney Docket Number	P118-US

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
LV	DL	WINTERS, H.F., "Etch Products from the Reaction of XeF ₂ with SiO ₂ , SiO ₃ , Si ₃ N ₄ , SiC, and Si in the Presence of Ion Bombardment", J. Vac. Sci. Technol. B 1(4) (Oct/Dec 1983), pp. 927-931.	
	DM	WINTERS et al., "The Etching of Silicon with XeF ₂ Vapor", Appl. Phys. Letter, Vol. 34(1) (January 1, 1979), pp. 70-73.	
	DN	XACTIX, Inc., Marketing Brochure (June 27, 1999).	
	DO	"Xenon Difluoride Isotropic Etch System: Seeing is Believing", Surface Technology Systems Ltd. brochure, Newport, UK (date unknown).	
	DP	Assorted promotional literature, Surface Technology Systems Ltd., Newport, UK (July 28, 1999).	
LV		Kurt Williams, Etch Rates for Micromachining Processing-Part II, 2003 IEEE, Pgs 761-778, Journal of Microelectromechanical Systems, Vol. 12, No. 6, December 2003.	

Examiner Signature		Date Considered	5/10/05
--------------------	---	-----------------	---------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Substitute for form 1449B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>			Complete if Known	
	Application Number	10/666,671		
	Filing Date	9/17/03		
	First Named Inventor	Shi		
	Group Art Unit	1765		
	Examiner Name	Not Yet Assigned		
	Attorney Docket Number	P118-US		
Sheet	7	of	10	

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
<div style="font-size: 2em; margin-top: 10px;">C</div> <div style="border-left: 1px solid black; height: 100px; margin-left: 10px;"></div>	BA	ANDERSON, H.M., "Plasma Diagnostics for Semiconductor Processing", 2000 Digest of the LEOS Topical Meetings (July 24 - 28, 2000), pp. 117-118 (abstract only).	
	BB	BARYSHEV et al., "Monitoring of SiO_2/Si Plasma Etching and End-Point Detection", Mikroelektronika (Russia), Vol. 25, No. 5 (Sep/Oct 1996), pp. 373-379 (abstract only).	
	BC	BASSOM et al., "Modeling and Optimizing XeF_2 -enhanced FIB Milling of Silicon", 25th International Symposium for Testing and Failure Analysis, Santa Clara, CA (Nov. 14 -18, 1999), pp. 255-261 (abstract only).	
	BD	BERG et al., "Real-Time Control of Etching Processes: Experimental Results", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 3213 (1997), pp. 249-260 (abstract only).	
	BE	CHAMBERS et al., "Endpoint Uniformity Sensing and Analysis in Silicon Dioxide Plasma Etching Using In Situ Mass Spectrometry", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 16, No. 6 (Nov/Dec 1998), pp. 2996-3002 (abstract only).	
	BF	CHAN et al., "Gas Phase Pulse Etching of Silicon for MEMS with Xenon Difluoride", Engineering Solutions for the Next Millenium: 1999 IEEE Canadian Conference on Electrical and Computer Engineering, Edmonton, Alberta, Vol. 3 (May 9 - 12, 1999), pp. 1637-1642 (abstract only).	
	BG	CHANG et al., "Gas-Phase Silicon Micromachining with Silicon Difluoride", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 2641 (1995), pp. 117-128 (abstract only).	
	BH	CHEN et al., "Spatially Resolved Endpoint Detector for Plasma Etcher", 1997 IEEE International Symposium on Semiconductor Manufacturing Conference Proceedings, San Francisco, CA (Oct. 6 - 8, 1997), pp. B45 - B48 (abstract only).	
	BI	CHU et al., "Controlled Pulse-Etching with Xenon Difluoride", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 1 (June 16 - 19, 1997), pp. 665-668 (abstract only).	
	BJ	HEINRICH et al., "Multichannel Process Monitor for Real-Time Film Thickness and Rate Measurements in Dry Etching and Deposition", Vacuum, Vol. 51, No. 4, (Dec. 1998), pp. 497-502 (abstract only).	
<div style="font-size: 2em; margin-top: 10px;">C</div>	BK	KOHLER et al., "Fabrication of Microlenses by Plasmaless Isotropic Etching Combined with Plastic Moulding", Sens. Actuators A, Phys. (Switzerland), Vol. A53, No. 1-3 (May 1996), pp. 361-363 (abstract only).	

Examiner Signature	Date Considered 5/14/05
--------------------	-------------------------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Substitute for form 1449B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>			Complete if Known		
Application Number	10/666,671				
Filing Date	9/17/03				
First Named Inventor	SH				
Group Art Unit	1765				
Examiner Name	Not Yet Assigned				
Attorney Docket Number	P118-US				
Sheet	8	of	10		

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
LV	BL	LI et al., "Mass Spectrometric Measurements on Inductively Coupled Fluorocarbon Plasmas: Positive Ions, Radicals and Endpoint Detection", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 17, No. 5 (Sept. 1997), pp. 2438-2446 (abstract only).	
	BM	LIAMANOND et al., "Production Data Based Optimal Etch Time Control Design for a Reactive Ion Etching Process", IEEE Trans. Semicond. Manuf., Vol. 12, No. 1 (Feb. 1999), pp. 139-147 (abstract only).	
	BN	LITVAK, H.E., "End Point Control Via Optical Emission Spectroscopy", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 14, No. 1 (Jan/Feb 1996), pp. 516-520 (abstract only).	
	BO	LU et al., "Effluent Monitoring with FTIR Spectroscopy for Low Open Area Oxide Etch Endpoint Detection", 8th International Symposium on Semiconductor Silicon, San Diego, CA, Vol. 2 (May 4 - 8, 1998), pp. 1250-1261 (abstract only).	
	BP	MAYNARD et al., "Plasma Etching of Submicron Devices: In Situ Monitoring and Control by Multi-Wavelength Ellipsometry", Thin Solid Films (Switzerland), Vol. 313-314, No. 1-2 (Feb. 1998), pp. 398-405 (abstract only).	
	BQ	MELVILLE et al., "Volatile Products and Endpoint Detection in Reactive Ion Etching of III-V Compounds with a Broad Beam ECR Source", Nuclear Instruments & Methods in Physics Research, Section B (Beam Interactions with Materials and Atoms), Vol. B106, No. 1-4 (Dec. 1995), pp. 179-182 (abstract only).	
	BR	MUTHUKUMARAN et al., "Gas-Phase Xenon Difluoride Etching of Microsystems Fabricated Through the Mital 1.5-μm CMOS Process", Can. J. Electr. Comput. Eng. (Canada), Vol. 25, No. 1 (Jan. 2000), pp. 35-41 (abstract only).	
	BS	PERRIN, J., "Mass Spectrometry of Reactive Plasmas", Plasma Processing of Semiconductors, Chateau de Bonas, France (June 17 - 28, 1996), pp. 397-431 (abstract only).	
	BT	RICHTER et al., "Exhaust Gas Monitoring: New Window Into Semiconductor Processing", Solid State Technol., Vol. 42, No. 5 (May 1999), pp. 61, 63-64, 68, 70-71 (abstract only).	
	BU	SAITO et al., "Low Temperature Plasmaless Etching of Silicon Dioxide Film Using Chlorine Trifluoride Gas with Water Vapor", J. Electrochem. Soc., Vol. 147, No. 12 (Dec. 2000), pp. 4630-4632 (abstract only).	
LV	BV	SEBEL et al., "Etching of Si Through a Thick Condensed XeF ₂ Layer", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 5 (Sep/Oct 2000), pp. 2090-2097 (abstract only).	

Examiner Signature	Date Considered
	5/10/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449B/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	10/666,671
		Filing Date	9/17/03
		First Named Inventor	Shi
		Group Art Unit	1765
		Examiner Name	Not Yet Assigned
Sheet	9	of	10
		Attorney Docket Number	P118-US

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
LV	BW	SEBEL et al., "Reaction Layer Dynamics in Ion-Assisted Si/XeF ₂ Etching: Temperature Dependence", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 6, (Nov. 2000), pp. 2759-2769 (abstract only).	
	BX	SEBEL et al., "Silicon Etch Rate Enhancement by Traces of Metal", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 17, No. 3, (May/June 1999), pp. 755-762 (abstract only).	
	BY	SUGANO et al., "Study on XeF ₂ Pulse Etching Using Wagon Wheel Pattern", Proceedings of the 1999 International Symposium on Micromechanics and Human Science: Towards the New Century, Nagoya, Japan (Nov. 23 - 26, 1999), pp. 163-167 (abstract only).	
	BZ	SUN et al., "Sensitive Plasma Etching Endpoint Detection Using Tunable Diode Laser Absorption Spectroscopy", Appl. Phys. Lett., Vol. 64, No. 21 (May 23, 1994), pp. 2779-2781 (abstract only).	
	CA	THOMAS et al., "Minimized Response Time of Optical Emission and Mass Spectrometric Signals for Optimized Endpoint Detection", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 14, No. 4 (July/Aug 1996), pp. 2531-2536 (abstract only).	
	CB	TODA et al., "Thin Beam Bulk Micromachining Based on RIE and Xenon Difluoride Silicon Etching", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 1 (June 16 - 19, 1997), pp. 671-674.	
	CC	VUGTS et al., "Si/XeF ₂ Etching: Reaction Layer Dynamics and Surface Roughening", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 14, No. 5 (Sep/Oct 1996), pp. 2780-2789 (abstract only).	
	CD	VUGTS et al., "Si/XeF ₂ Etching: Temperature Dependence", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 14, No. 5 (Sep/Oct 1996), pp. 2766-2774 (abstract only).	
	CE	WAN et al., "Electron Cyclotron Resonance Plasma Reactor for SiO ₂ Etching: Process Diagnostics, End-Point Detection, and Surface Characterization", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 13, No. 4 (July/Aug 1995), pp. 2035-2043 (abstract only).	
	CF	WANG et al., "Gas-Phase Silicon Etching with Bromine Trifluoride", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 2 (June 16 - 19, 1997), pp. 1505-1508 (abstract only).	
LV	CG	WARD, P.P., "Plasma Process Control with Optical Emission Spectroscopy", 17th IEEE/CPMT International Electronics Manufacturing Technology Symposium: Manufacturing Technologies - Present and Future, Austin, TX (Oct. 2 - 4, 1995), pp. 166-169 (abstract only).	

Examiner Signature		Date Considered	5/10/05
--------------------	---	-----------------	---------

¹ EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

² Applicant's unique citation designation number (optional). ³ Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

Substitute for form 1449B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>			Complete if Known	
	Application Number	10/666,671		
	Filing Date	9/17/03		
	First Named Inventor	Shi		
	Group Art Unit	1765		
	Examiner Name	Not Yet Assigned		
Sheet	10	of	10	Attorney Docket Number P118-US

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
<div style="font-size: 2em;">↓</div>	CH	WARNEKE, et al., "In Situ Characterization of CMOS Post-Process Micromachining", Sens. Actuators A, Phys. (Switzerland), Vol. A89, No. 1-2 (March 20, 2001), pp. 142-151 (abstract only).	
	CI	WELCH et al., "Breaking the 0.5 Percent Exposed Area Etch Endpoint Barrier", Semicond. Int., Vol. 19, No. 8 (July 1996), pp. 269-270, 272, 274, 276 (abstract only).	
	CJ	WODECKI, N.D., Low Open Area Multi-Layered Dielectric Film Etch Endpoint Detection Using EndPoint Plus (TM)", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 3882 (1999), pp. 231-238 (abstract only).	
	CK	WONG et al., "Endpoint Prediction for Polysilicon Plasma Etch Via Optical Emission Interferometry", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 15, No. 3, Pt. 2 (May/June 1997), pp. 1403-1408 (abstract only).	
	CL	YUE et al., "Plasma Etching Endpoint Detection Using Multiple Wavelengths for Small Open Area Wafers", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 19, No. 1 (Jan. 2001), pp. 66-75 (abstract only).	

Examiner Signature	Date Considered 5/10/05
--------------------	-------------------------

¹ EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.